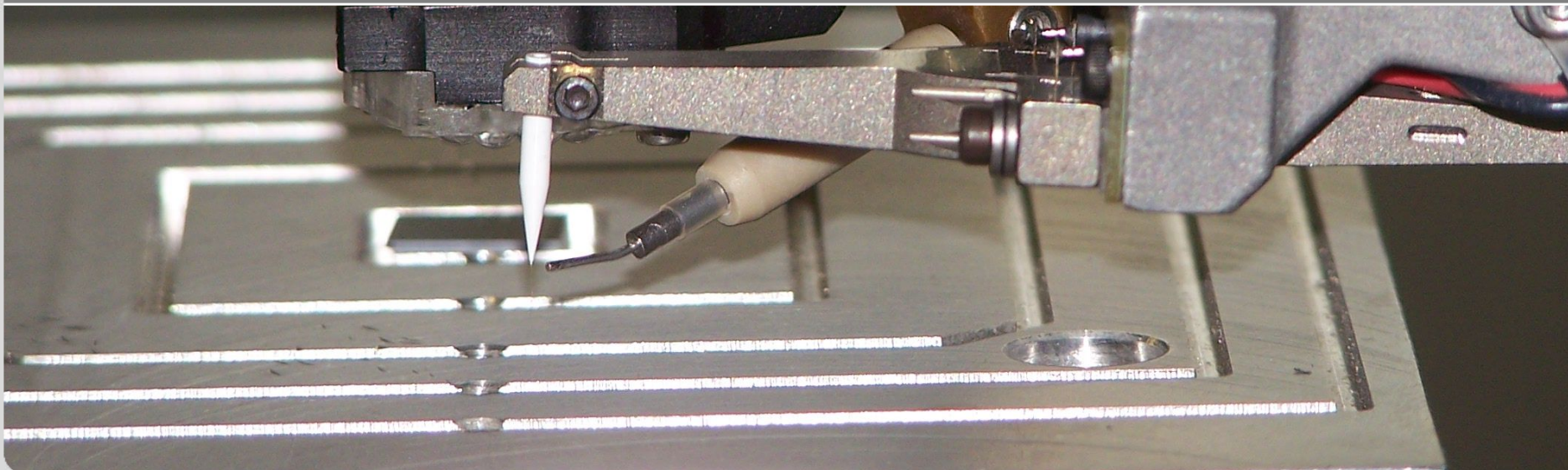


Gold-stud bumpbonding

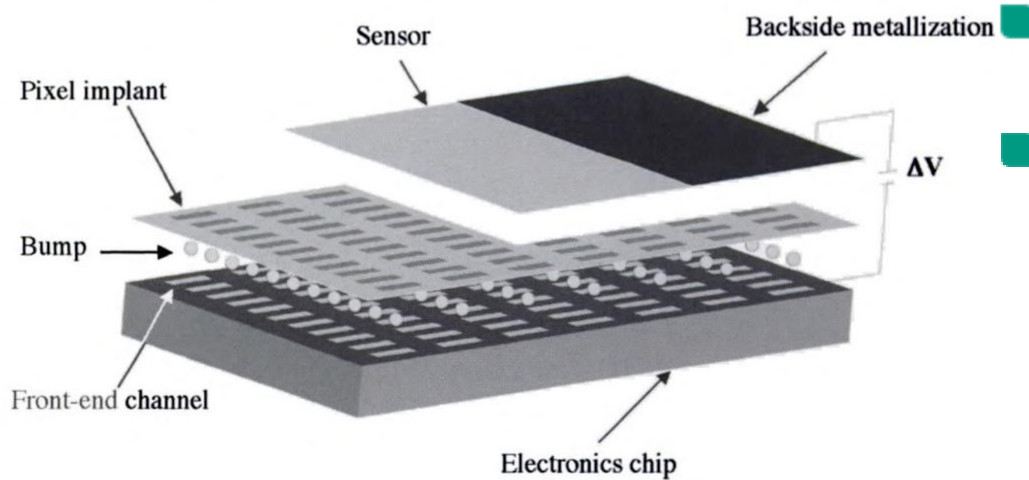
Interconnection technology for research and development of new detectors

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Institut für Experimentelle Kernphysik

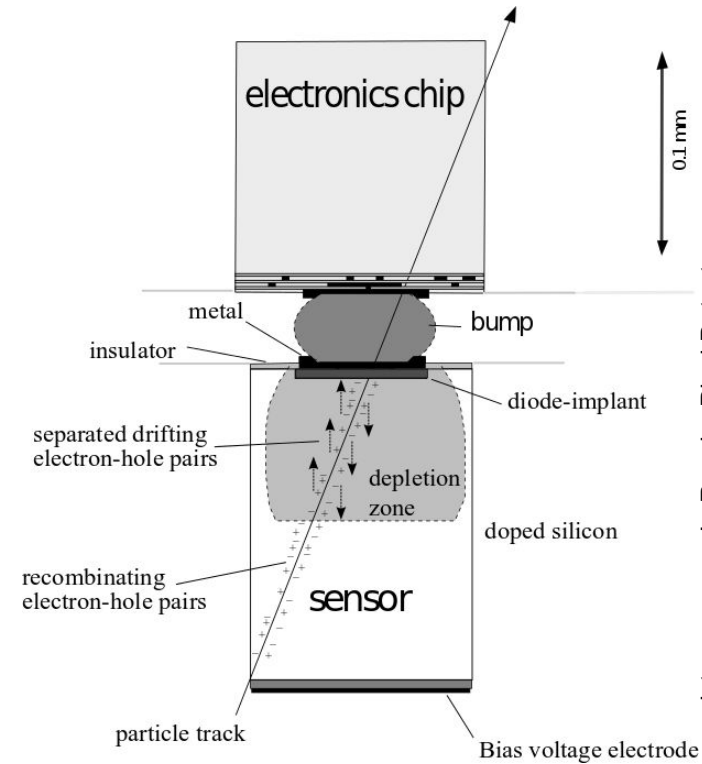


Bumpbonding of pixel detectors



- Interconnection-density of pixel detectors **to high** for wire bonding
- Bumpbonding for vertical interconnection with **high** density

- Standard technologies base on chemical bump deposition
- Chemical processes need Under-Bump-Metallization (UBM)
- **Complex and expensive** wafer-processing
- Search for cheap and flexible bumpbonding alternative technologies for single chip processing during R&D



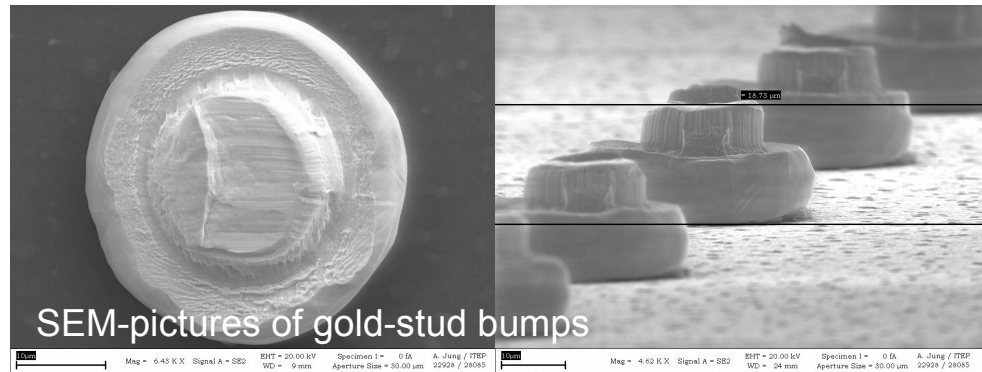
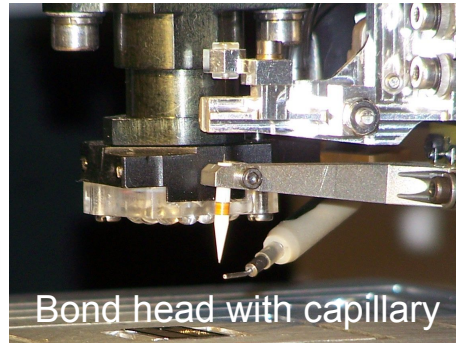
picture-source: L. Rossi – Pixel Detectors

Alternative bumping method (KIT)

- Gold-stud bumping is an evolution of ~50 years of wirebonding
- Wire gets sheared after ball connection to substrate



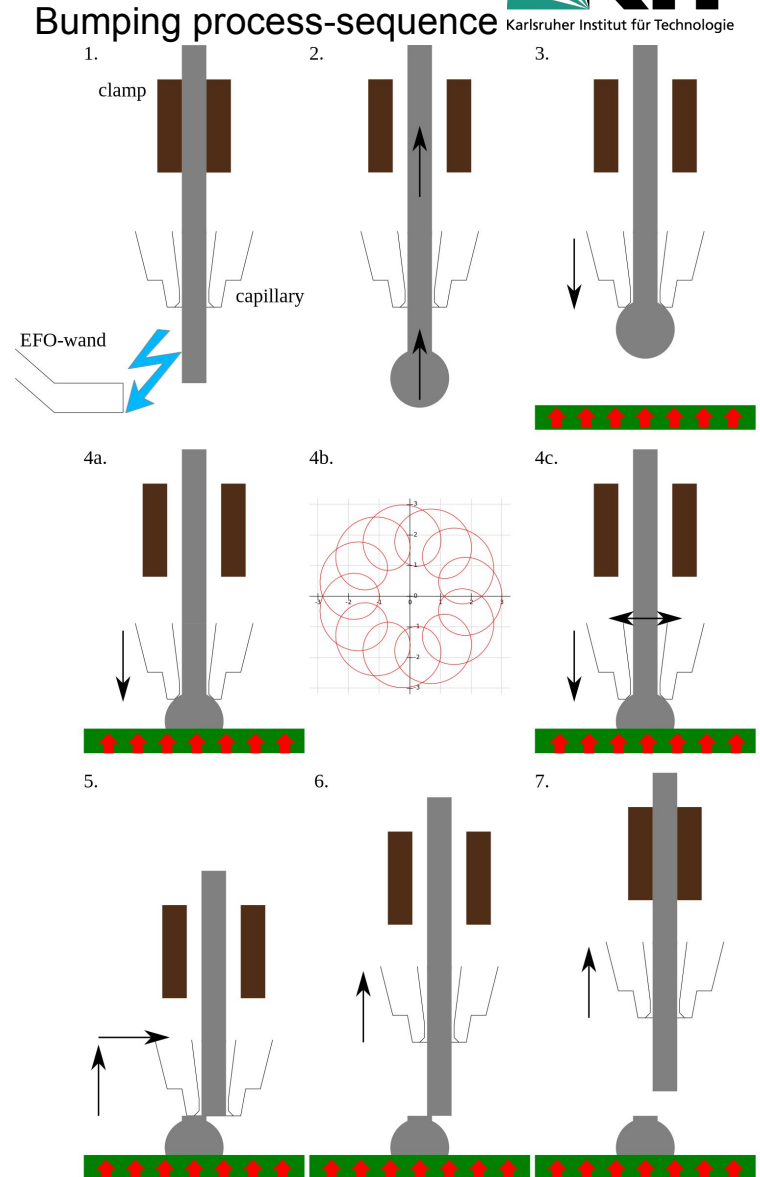
- No UBM necessary
- Single-chip-bumping possible
- Cheap bumping process, @KIT
- 20 bumps/s



Bumping – process operation

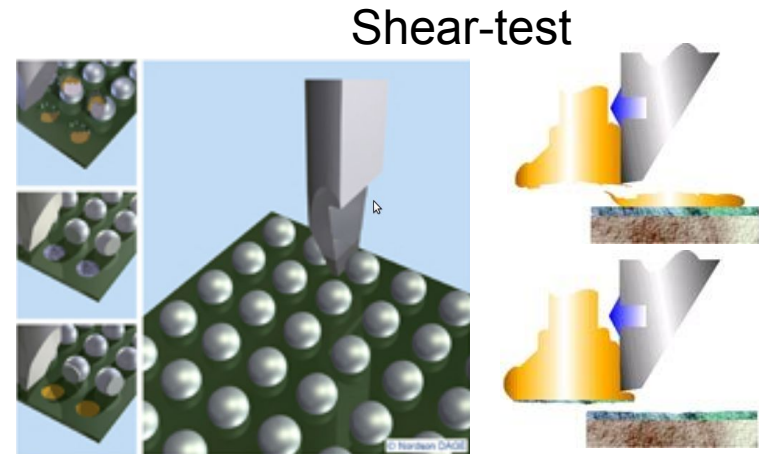
- Process of upto 10 single steps
 - "Free Air Ball" formation
 - Touchdown onto surface
 - Bonding via ultrasonic bonding by ultrasonic generator (USG)
 - Shearing of wire
 - Re-feeding and ripping of wire

- Process with **large number** of parameters → optimization regarding:
 - Mechanical strength
 - Bumpsize and -shape
 - Long-term stability



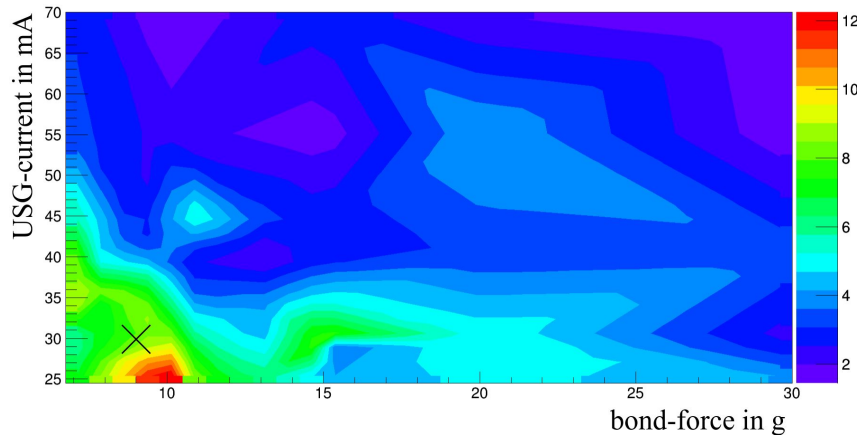
Bumping – mechanical strength

- Investigation by shearing of the bumps
- Looking for:
 - High shearforce per connection area
 - Separation process: bond-shear, aluminium-shear



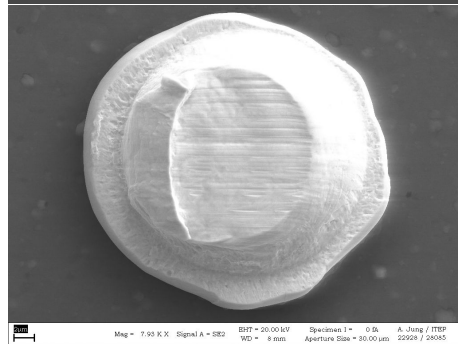
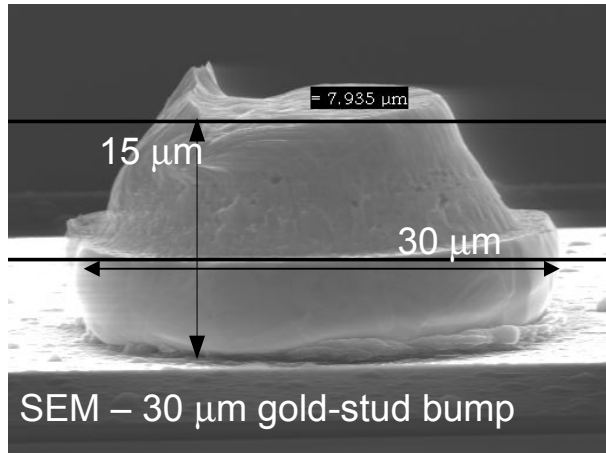
Picture sources: SPT & Nordson

$$\gamma = \frac{\overline{F}_{shear}}{A_{connection} \cdot \sigma(F_{shear})}$$



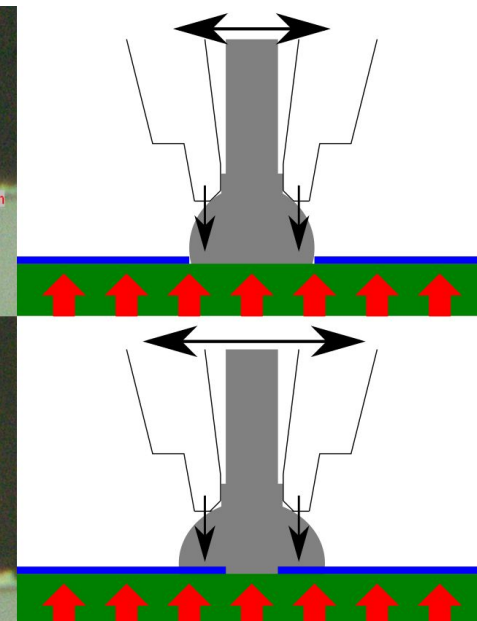
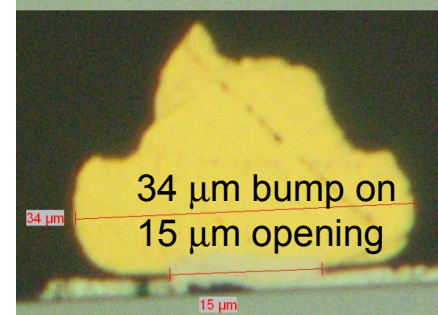
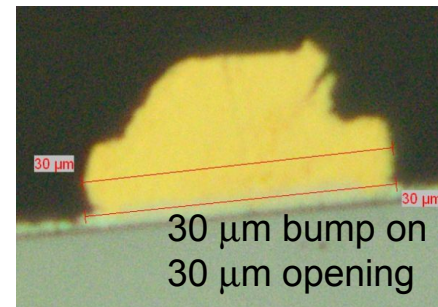
- Systematical investigation of mechanical strength
- No connection for $I_{USG} < 25$ mA or $F_{bond} < 7$ g
- Dimension for mechanical strength $\gamma = \overline{F} / (A\sigma)$, σ = standard deviation
- Parameters in area of **high stability** chosen
- Shearforce: **8 g per bump**

Bumping – Bumpgröße & -form



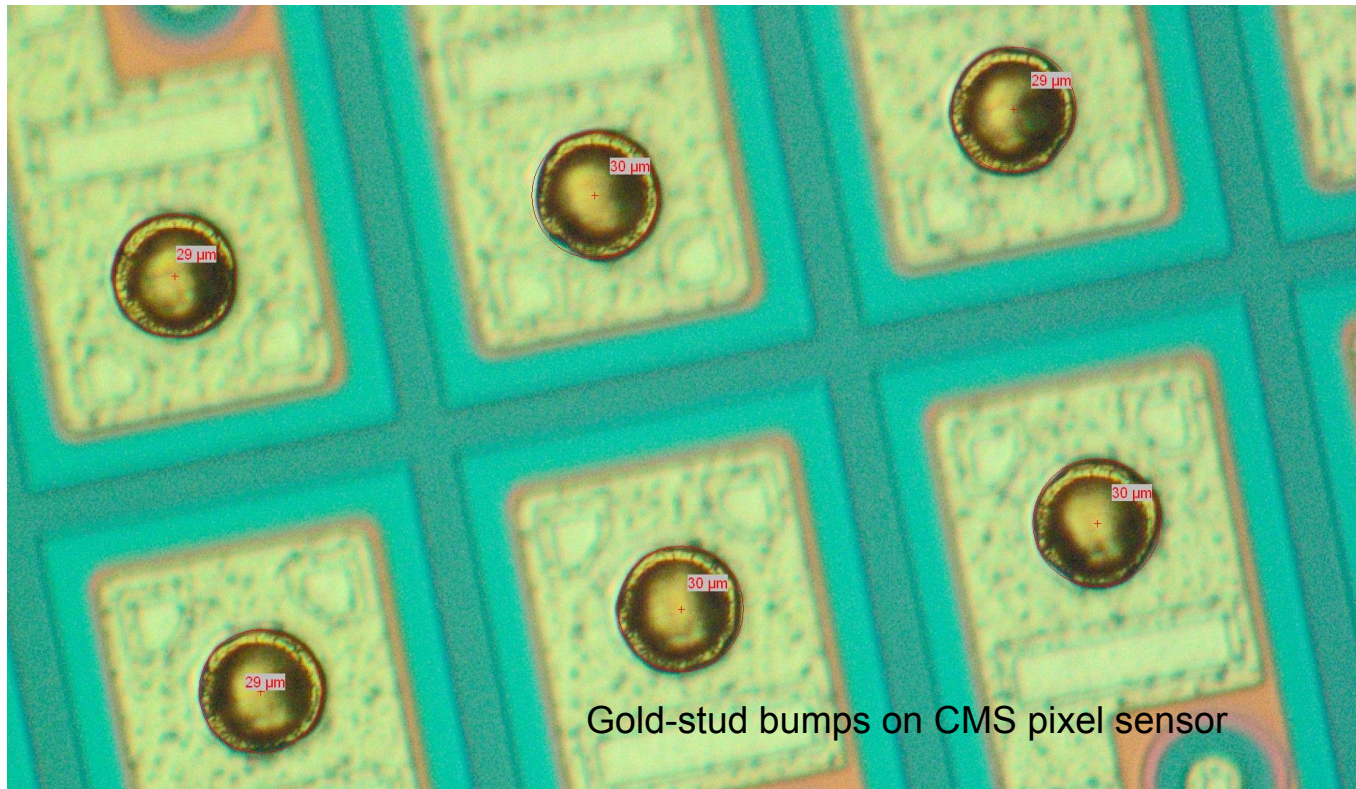
- Bump-shaping via wire-shearing parameters
- Current status: 30 µm diameter, 15 µm height
- Bump-diameter comparable to lithographic process

- Minimal bump-diameter depending on opening diameter of passivation → **small passivation openings cause bigger bumps**

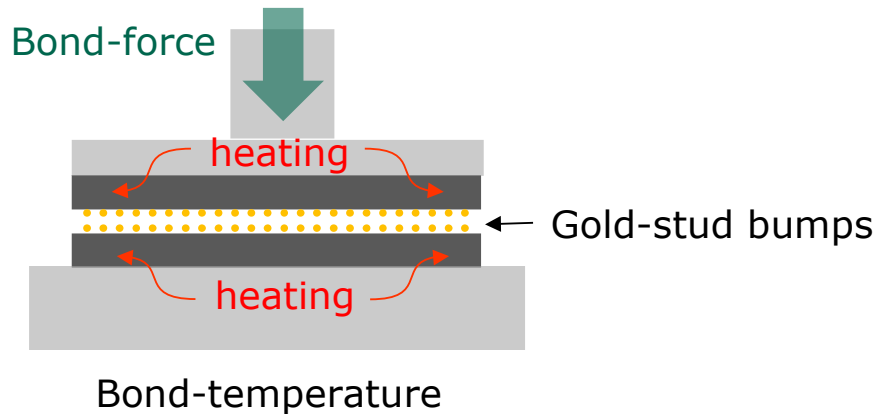


Bumping – long-term stability

- Long-term stability depending on hardware parameters (condition of wire , cleanliness of wire-feed system) **and** bumping parameters
- Current long-term stability **>4000 bumps** without interruption → bumping of a CMS pixel single sensor (4160 bumps) process in **<5 min**



Bonding – process operation



Two-step process

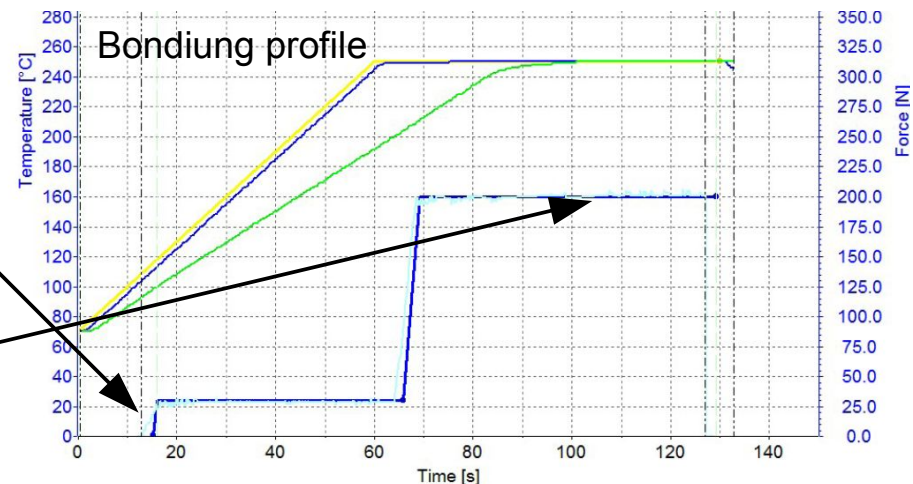
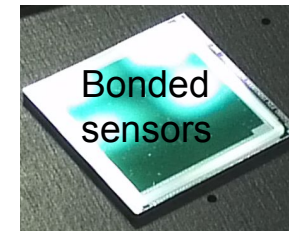
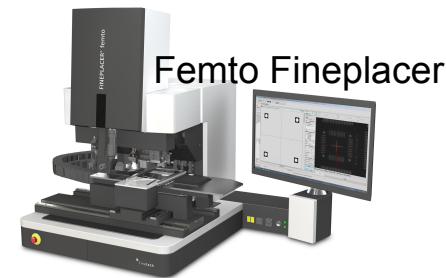
- 1) Establishing planarity by gamber tool
- 2) Bonding by thermo compression

Process parameters

- 1) Bond-force: 200 N (4,9 g/bump) for 60 s (necessary for bumpdeformation)
- 2) Bond-temperature 250 °C for 60 s (no elektromigration in ROC/Sensor)

- Flip-chip bonding by thermo-compression

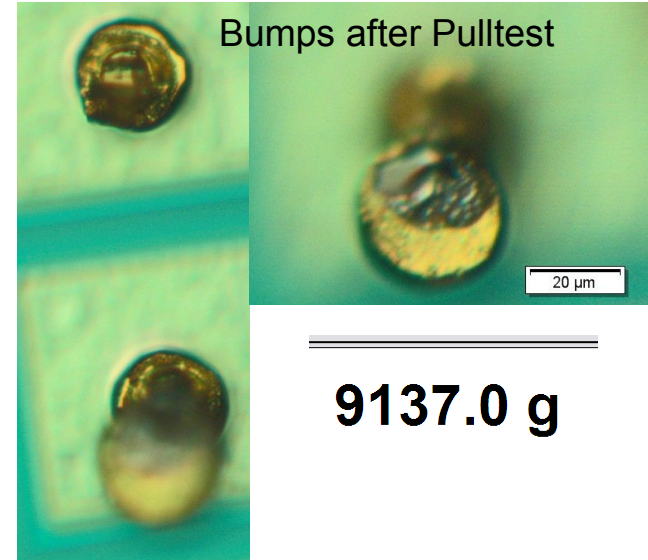
- Bonding with Femto Fineplacer® @KIT



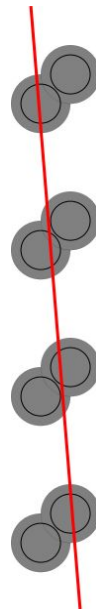
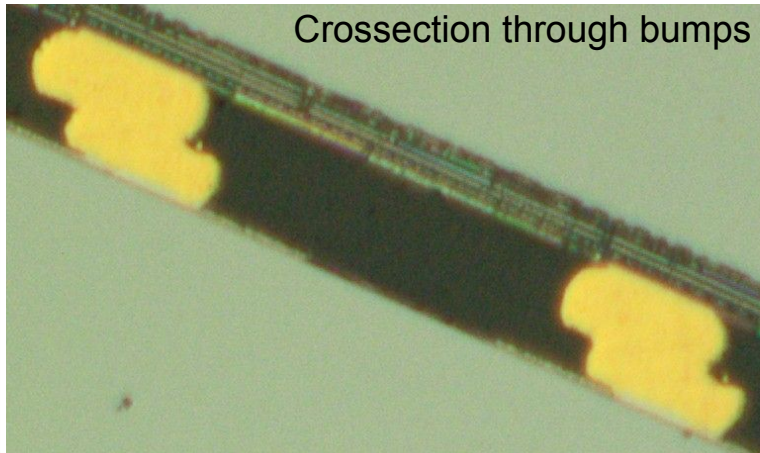
Bonding – test results

■ Pulltest:

- High pull force of **>2,2 g** per bump
- Separation process: 95% bump-to-bump, 5% aluminium-liftoff
 - **bumping** optimized
 - **bonding** not optimized yet
- **Chip shift** due to weak vacuum



Crossection through bumps



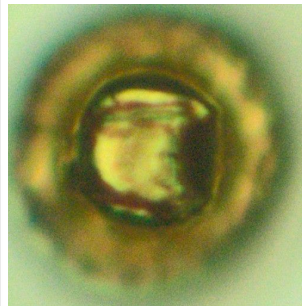
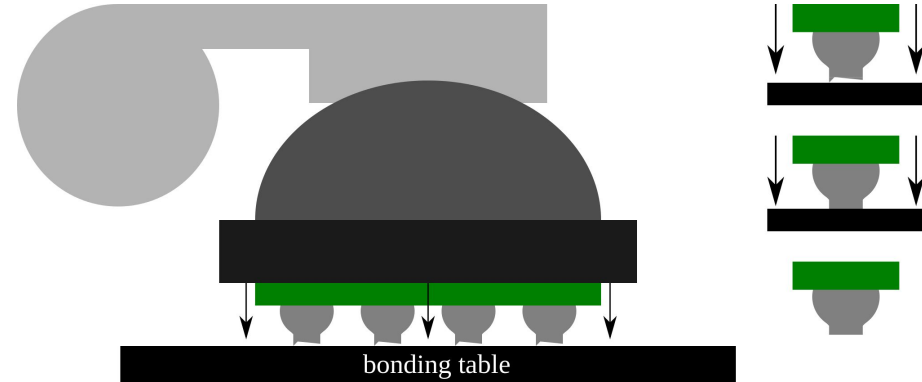
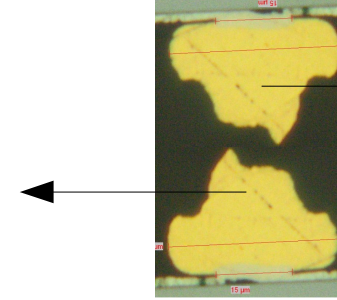
■ Cross-section:

- **Very good connection** of the gold bumps at 250 °C
- **Chip shift** due to weak vacuum

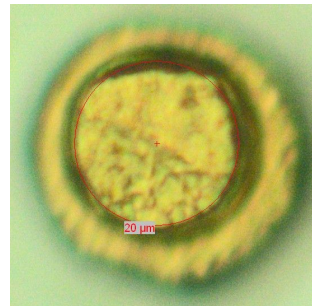
Bonding – flattening of bumps

- Shift due to **high shear-forces** during the bonding
→ **Reduction of the shear-forces** by flattening all bumps
- Pressing bumps onto bonding table

Cross-section of bump



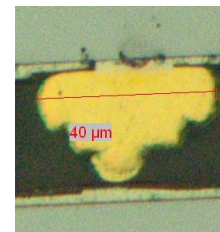
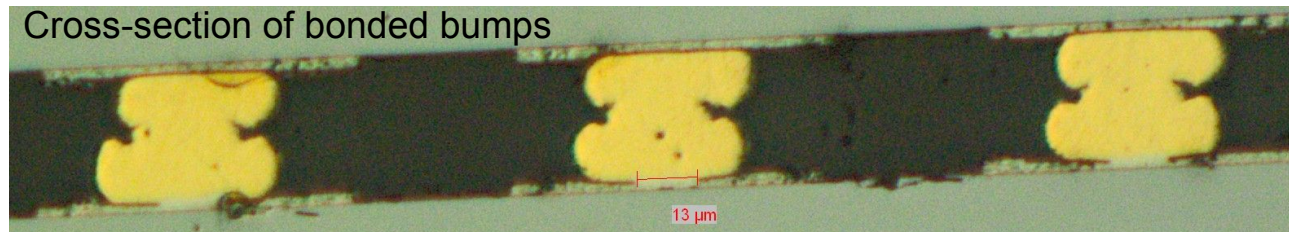
Gold-stud surface



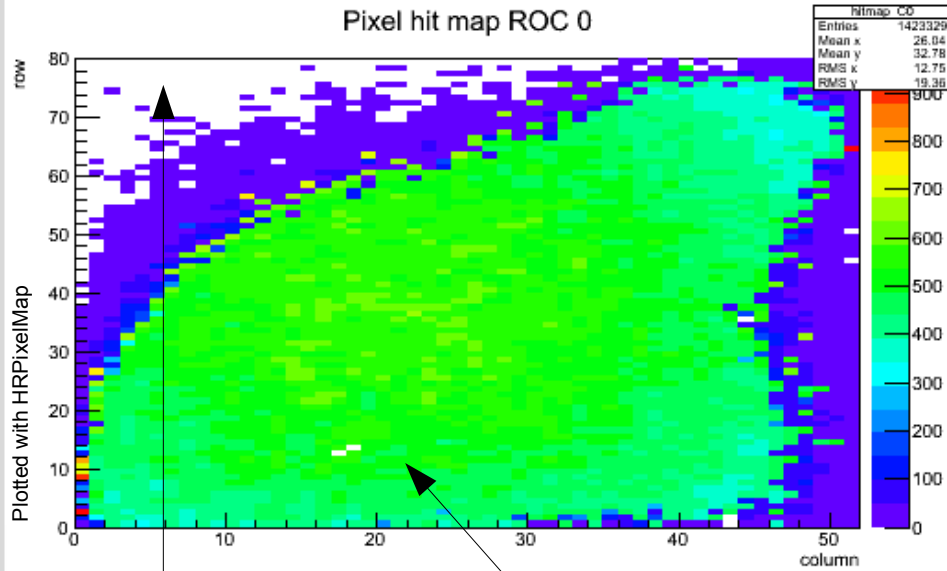
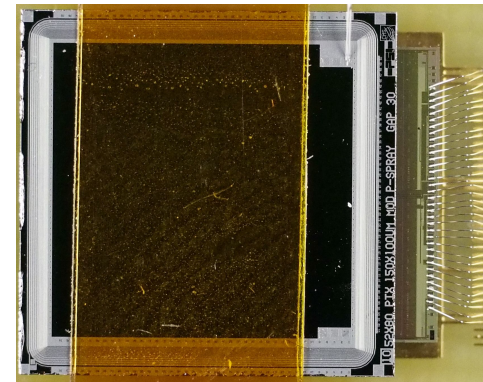
- **Shift reduced**
- All bumps seem to be **connected** → electrical test



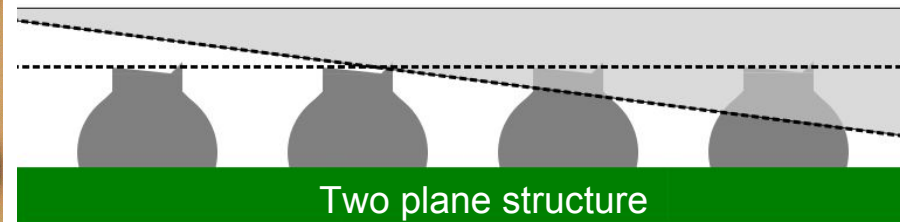
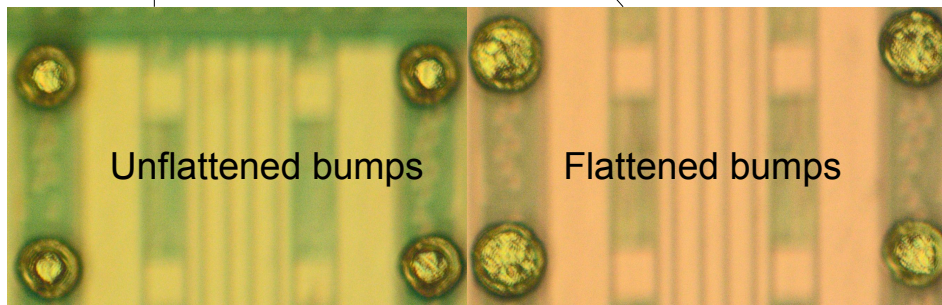
Cross-section of bonded bumps



Bonding – electrical test



- First prototype assembled
- Chip alive after processing and 80% of connections established
- Source test shows **planarity problem**
 - correlated to **flattening problem** causing **two plane** structure
- Improving flattening process to assemble class A singles **soon**



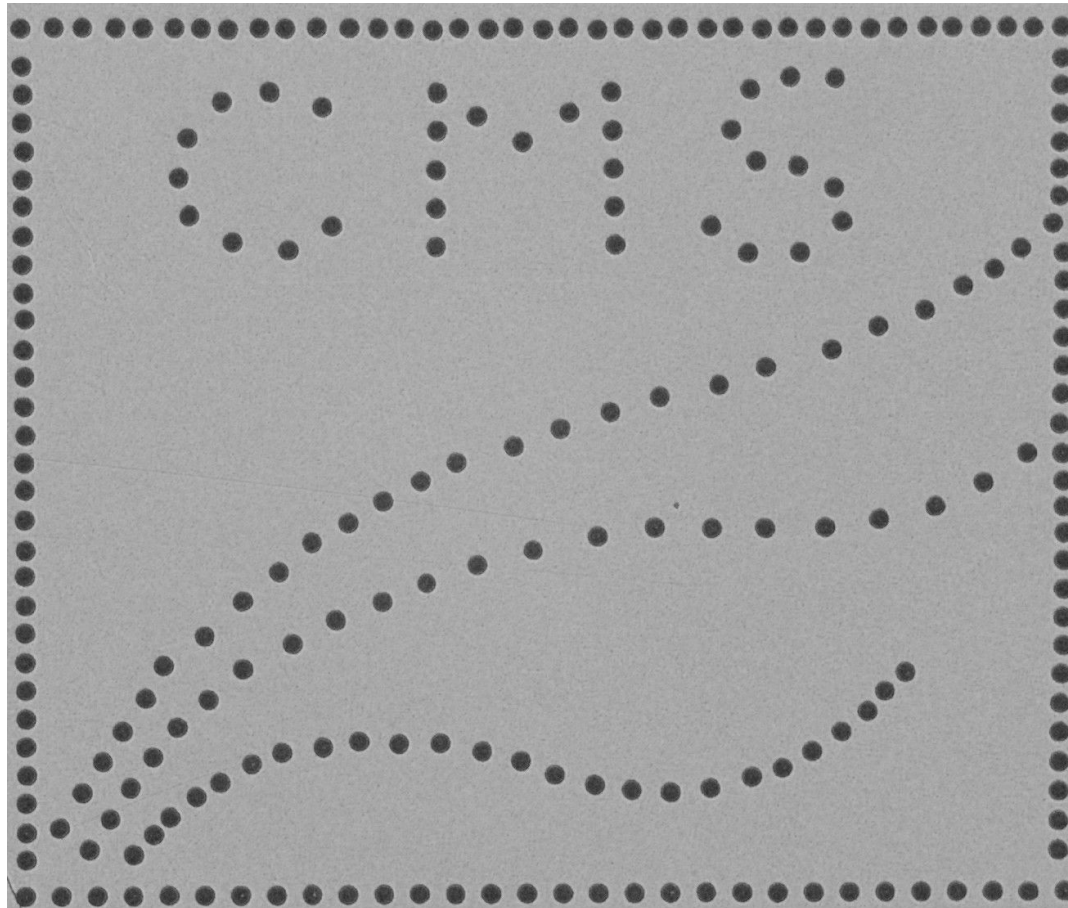
Summary

- Bumpbonding necessary for hybrid pixel detectors but complex and expensive
- Gold-stud bumpbonding as cheap flexible alternative that enables single-chip processing in the R&D phase

- Setting at KIT:
 - Bumping with Ball-wedge bonder (@KIT)
 - Bonding with Flip-chip bonder (@KIT) } Bumpbonding process @KIT

- Status:
 - Stable process producing 30- μ m-bumps
 - Very good and strong interconnection using 250 °C bond-temperature
 - Chip shift due to weak vacuum → flattening of bumps to avoid shear forces

- Upcoming:
 - Improvement of flattening process and produce class A singles



Thanks for your attention!